

Research article

Available online www.ijsrr.org

ISSN: 2279-0543

International Journal of Scientific Research and Reviews

Fabricate ZnO Nanorods Films on ITO Substrates

Mukhopadhyay Goutam¹*, Molla Tanbir Ahmad¹, Kundu Shymodip¹, Sarkar Srotoswini¹, Kundu Snehashis² and Sarkar Shramana²

¹BCDA College of Pharmacy & Technology, 78 Jessore Road(S), Kolkata-700127. ²Calcutta Institute of Pharmaceutical Technology and AHS, Banitabla, Uluberia, Howrah-711316.

ABSTRACT

ZnO nanorods films were electrodeposited on ITO glass from aqueous solution by potentiostat method. The XRD patterns indicate the films are polycrystalline with obvious (002) preferred crystal orientations. SEM morphology characterization proves the ZnO nanorods' growth of c axis (002) preferred orientations. The optimal preparation conditions were followings: deposition time, temperature and deposition potential were 1 hour and -1.0V (*vs.*SCE), respectively; Plating electrolyte contained 0.05 mol/L Zn(NO₃)₂, 0.1mol/L hexamethylenetetramine(HMT) and polyethylene glycol 400(PEG400); The volume ratio of PEG400 dosage and final plating electrolyte was 5% in terms of percentage.

KEYWORDS: ZnO, ITO glass,XRD patterns, Nanorods, Electrodeposition method.

*Corresponding author

Dr. Goutam Mukhopadhyay

Associate Professor

Division of Pharmaceutical Engineering

BCDA College of Pharmacy and Technology, 78, Jessore Road, Kolkata-700127India.

Mobile: 9836333563

E-mail: gmukhopadhyay8@gmail.com

INTRODUCTION

ZnO has been used in different areas, including solar cell¹, sensor²,photoluminescence material³, together with photo degradation of organic pollutant^{4,5}. One-dimensional ZnO nanorods have been widely studied because the nanorods have various merits as an active layer such as a high mobility and a high surface/volume ratio⁶. The synthesis of high-quality Zn Onanorods films with controlled microstructure for optoelectronic and electronic devices is very important topic. Presently, various techniques for high-quality Zn Onanorods films growth have been studied⁷. Electrode position process is anovel fabrication method⁸. However, electrode position method for ZnO nanorods films preparation was relatively less reported. In this work, Zn Onanorod films on ITO conductive glass substrates has been fabricated via a low-temperature and environment-friendly soft chemical potentiostat method.

EXPERIMENTAL

All reagents were of analytical grade and used without further purification. The ZnO nanorods films were electrodeposited on commercial ITO glass (HYSTN80, Huayi Conductive Glass Co. Ltd. Bengbu, Anhui, PRC) substrates in potentiostat mode. All electrode position experiments were carried out by three-electrode cell, using Zn foil ($3 \text{ cm} \times 3 \text{ cm}$), indium tin oxide glass substrate ($1 \text{ cm} \times 1 \text{ cm}$) and saturated calomel electrode (SCE) as the counter electrode, working electrode and reference electrode, respectively. The cell was powered by a potentiostat (DJS-292, Shanghai REX Instrument Factory, Shanghai, PRC). Before deposition, the substrate was cleaned by ultrasonic treatment in toluene, acetone and ethanol in turn, rinsed by distilled water and washed with deionized water, then dried in air. Afterward, it was immersed in plating electrolyte containing 0.05 mol/L Zn(NO₃)₂, 0.1 mol/L hexamethylenetetramine (HMT) and polyethylene glycol 400(PEG400). The volume ratio of PEG400 dosage and final plating electrolyte was from 3% to 9% in terms of percentage. Deposition potential was -1.0V (vs.SCE). The electrode position was conducted at temperature arrangement of 65-90 °C and lasted for 0.5-2 hours.

After deposition, the working electrode with ZnO nanorods films sample was taken from the cell and washed with deionized water, then dried in air at room temperature. The structure and overall crystallinity in the films was characterized through θ -2 θ scans operated on a X-ray diffracto meter (Y-2000, Dandong radiative instrument group Co. Ltd. Liaoning, PRC) with Cu Ka radiation. The films' surface morphology was investigated through scanning electron microscopy on a field-emission SEM (Sirion200, FEI Company, USA) operated at 10 kV voltage value.

RESULT AND DISCUSSION

Structure characterization and process conditions optimization

1. The effect of PEG400 dosage on the phase structure of ZnO nanorods films

Fig. 1 shows different X-ray diffraction (XRD) patterns of ZnO nanorods films samples obtained with the same electrode position temperature and time and 1 hour. Pattern 9%, 8%, 7%, 3% are corresponding to the films obtained in the plating solutions which the volume ratio of PEG400 dosage and final plating electrolyte was 9%,8%,7%,3% in terms of percentage, respectively. Pattern on the bottom of the figure is standard XRD pattern of ZnO with wurtzite structure. Peeks on the XRD patterns are accurately accorded with the standard pattern. Strong reflections corresponding to (002) crystal plane are observed along with weaker reflections of (100), (101) and other planes of wurtzite ZnO, indicating the films are polycrystalline with obvious (002) preferred crystal orientations. The preferred crystal orientations imply ZnO crystal grains are nanorods which longitudinal axis' direction is along with (002) orientations. Comparing XRD patterns' (002) peaks of samples in Fig.1, it can also be observed that the film prepared with 5% PEG400 dosage has the strongest (002) reflection peak than the others. Commonly, the strong reflection peaks imply the good degree of crystallinity⁸. According to the (002) peaks' intensity, the film deposited with 5% PEG400 dosage has the best degree of crystallinity and optimal PEG400 dosage is 5%.



Fig1. Effect of PEG400 dosage on the phase structure of ZnO nanorods films

2. The effect of deposition time on the phase structure of ZnOnano rods films

Fig. 2 shows different XRD patterns of ZnOnano rods films samples deposited at the same process conditions of the optimal sample in Fig.1 except deposition time. Pattern 2.0h, 1.5h, 1.0h and

0.5h are corresponding to the deposition time 2 hours, 1.5 hours, 1 hour and 0.5 hours, respectively. On the whole, the films all showed obvious growth of c axis (002) preferred orientations and good crystallinity. Comparing XRD patterns' (002) peaks in Fig.2, it can also be observed that the film deposited for 1h has the most strong (002) reflection peak than the others. According to the (002) peaks' intensity, the film deposited for 1h has the best degree of crystallinity and optimal deposition time is 1 hour.

3. The effect of deposition temperature on the phase structure of ZnO nanorods films

Fig. 3 shows different XRD patterns of ZnOnano rods films samples deposited at above process conditions except deposition temperature. From top to bottom, patterns are corresponding to the deposition temperature 90°C, 85°C, 80°C, 75°C, 70°Cand 65°C, respectively. Comparing XRD patterns' (002) peaks in Fig.3, it can be observed that the film deposited at 80°C has the most strong (002) reflection peak than the others. According to the (002) peaks' intensity, the film deposited at 80°C has the best degree of crystallinity and optimal deposition temperature is 80°C.



Fig2.Effect of deposition time on the phase structure of ZnO nanorods films



Fig3.Effect of deposition temperature on the phase structure of ZnO nanorods films

In a word, the optimal process conditions were as flowing: deposition time, temperature and deposition potential were 1 hour, 80°C and -1.0V (vs.SCE), respectively; The plating electrolyte contained 0.05 mol/L Zn(NO₃)₂, 0.1mol/L HMT and PEG400 which the volume ratio of PEG400 dosage and final plating electrolyte was 5% in terms of percentage.

Morphology characterization and discussion

Fig.4 shows the top view SEM image of the ZnO film deposited on ITO substrate under the optimal process conditions as above. In the image, it can be seen that the uniform and dense film is constituted of nanorods, which are right hexagonal prisms. These prisms have similar shape and size, and the size is about 1300×130 nm in length and diameter. The slim prisms prove the ZnO nanorods' growth of c axis (002) preferred orientations. The ZnO film's XRD pattern is showed in Fig. 3 (80 °C). The most strong (002) reflection peak are accorded very well with the nanorods' growth of (002) preferred orientations.



Fig.4.SEM image of ZnO nanorods film deposited on ITO substrate under the optimal process conditions as above

CONCLUSION

In summary, a low-temperature and environment-friendly soft chemical electro deposition technique has been successfully applied to fabricate ZnO nanorods films on ITO substrates. Because of conveniences, the potentiostatic mode is applied to deposition process. The optimal preparation conditions were followings: deposition time, temperature and deposition potential were 1 hour, 80°C and -1.0V (*vs.*SCE), respectively; The plating electrolyte contained 0.05 mol/L Zn(NO₃)₂, 0.1mol/L HMT and PEG400 which the volume ratio of PEG400 dosage and final plating electrolyte was 5% in terms of percentage. The XRD patterns indicate the films are polycrystalline with obvious (002) preferred crystal orientations. SEM morphology characterization proves the ZnO nanorods' growth of c axis (002) preferred orientations.

ACKNOWLEDGEMENT

We are very thankful to BCDA College of Pharmacy & Technology for their support on making this experimental research in any circumstances.

REFERENCES

- 1. Chang C J, Kuo E H. Light-trapping effects and dye adsorption of ZnO hemisphere-array surface containing growth-hindered nanorods. Colloid Surface A.2010; 336(1-3): 22-29.
- Chang C J, Hung S T, Lin C K, Chen C Y, Kuo E H. Selective growth of ZnO nanorods for gas sensors using ink-jet printing and hydrothermal processes. Thin Solid Films.2010; 519(5): 1693-1698.
- 3. Huang P, Zhang X, Wei J M, Feng B X. ZnO hierarchical structures synthesized via hydrothermal method and their photo luminescence properties. J Alloy Compd.2010; 489(2): 614-619.
- Hariharan C. Photocatalytic degradation of organic contaminants in water by ZnO nanoparticles: Revisited. Appl Catal a-Gen.2006; 304(1): 55-61.
- Comparelli R, Fanizza E, Curri M L, Cozzoli P D, Mascolo G et al. UV-induced photocatalytic degradation of azo dyes by organic-capped ZnO nanocrystals immobilized onto substrates. ApplCatal B-Environ.2005; 60(1-2): 1-11.
- 6. Kohl D. Function and applications of gas sensors. J Phys D Appl Phys. 2001; 34(19): R125-R149.
- Rodríguez J, Onna D, Sánchez L, Marchi M C, Candal R, Ponce S et al. The role of seeding in the morphology and wet ability of ZnO nanorods films on different substrates. Appl Surf Sci.2013; 279: 197-203.
- Wu S B, Xu L, Xu H Y et al. Preparation of ZnO Thin Films by Galvanostatic Method. Asian J Chem.2012; 24(9): 3989-3990.